



Génie Electrique et Electronique
Master Program
Prof. Elison Matioli

EE-557 Semiconductor devices I

Power semiconductor devices

Outline of the lecture

Basics of power devices

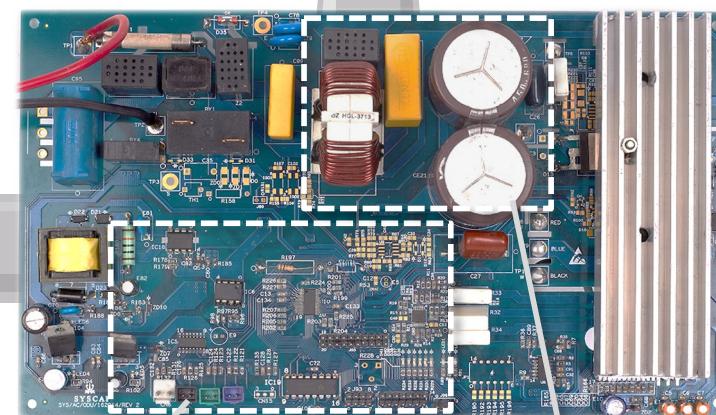
- Baliga's figure of merit
- Power diodes
- Power MOSFETs
- IGBTs

References:

Chapter 4.2 of Fundamentals of Power Electronics – second edition – Robert W. Erickson and Dragan Maksimović, Kluwer Academic Publishers, 2004

- How can semiconductor devices hold large voltages for power applications?
- How is the voltage related to the semiconductor properties?
- What are the different types of semiconductor power devices?

Power Electronics

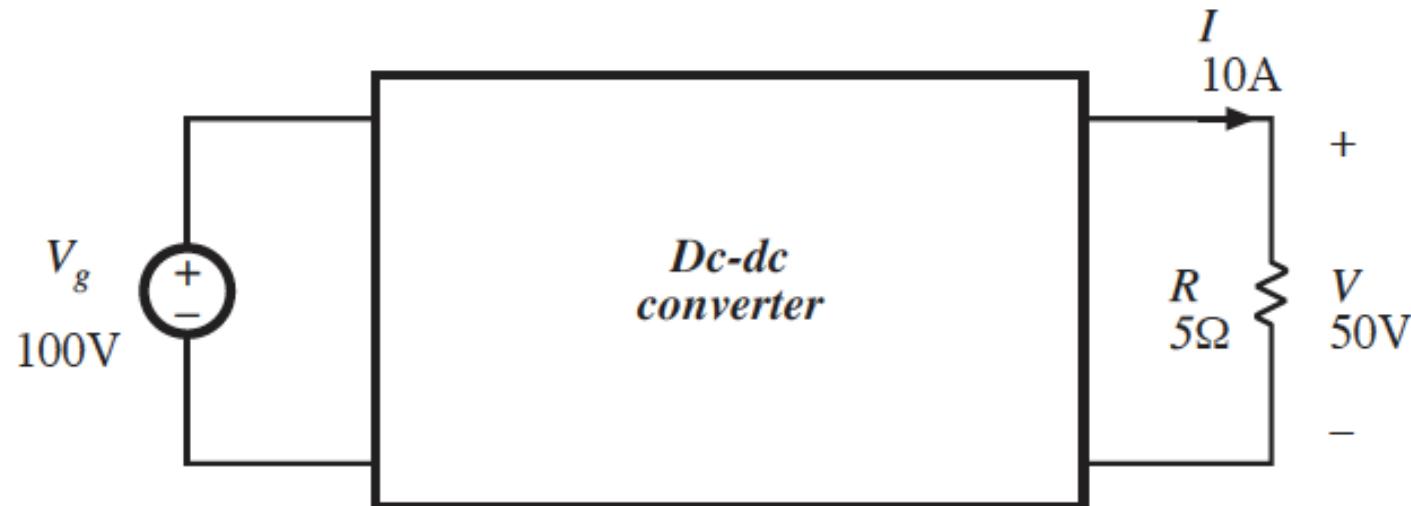


Semiconductor devices:
transistors, diodes, and
thyristors

Passive components:
capacitors, inductors,
transformers, etc.

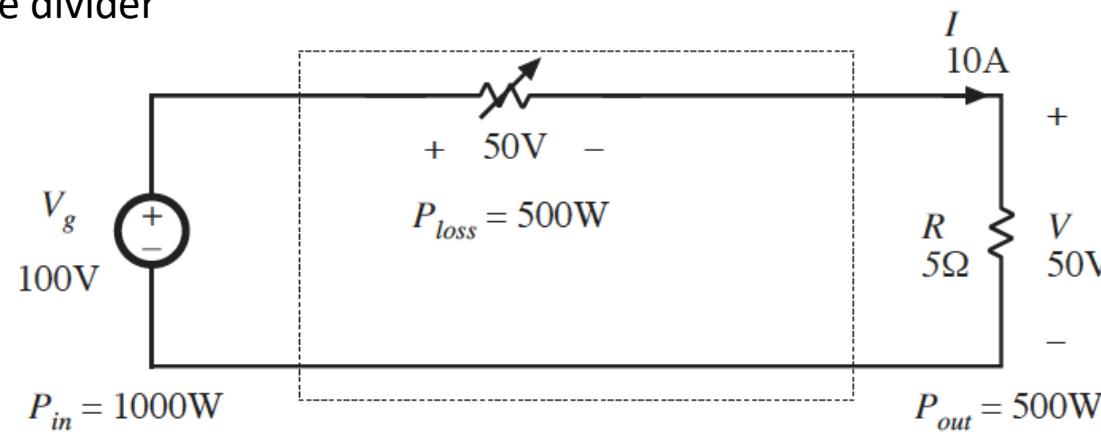


DC-DC converter

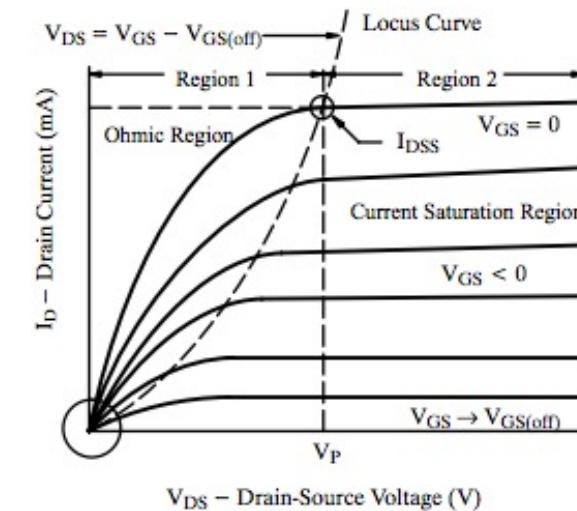
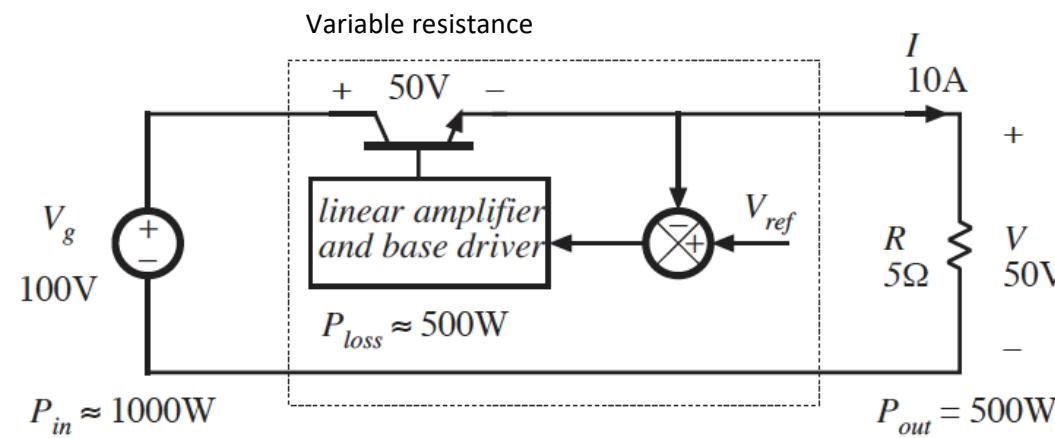


How can such converter be realised?

Solution 1: voltage divider

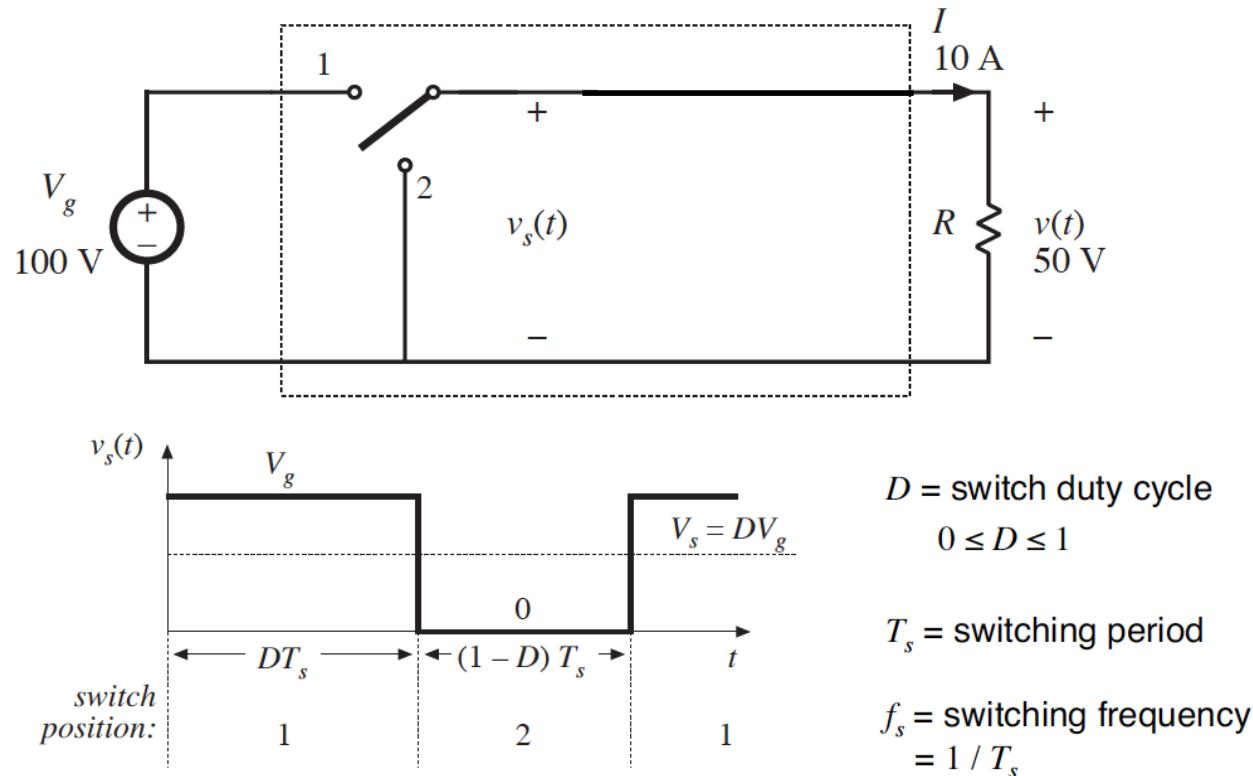


Solution 2: linear amplifier



These are very inefficient solutions

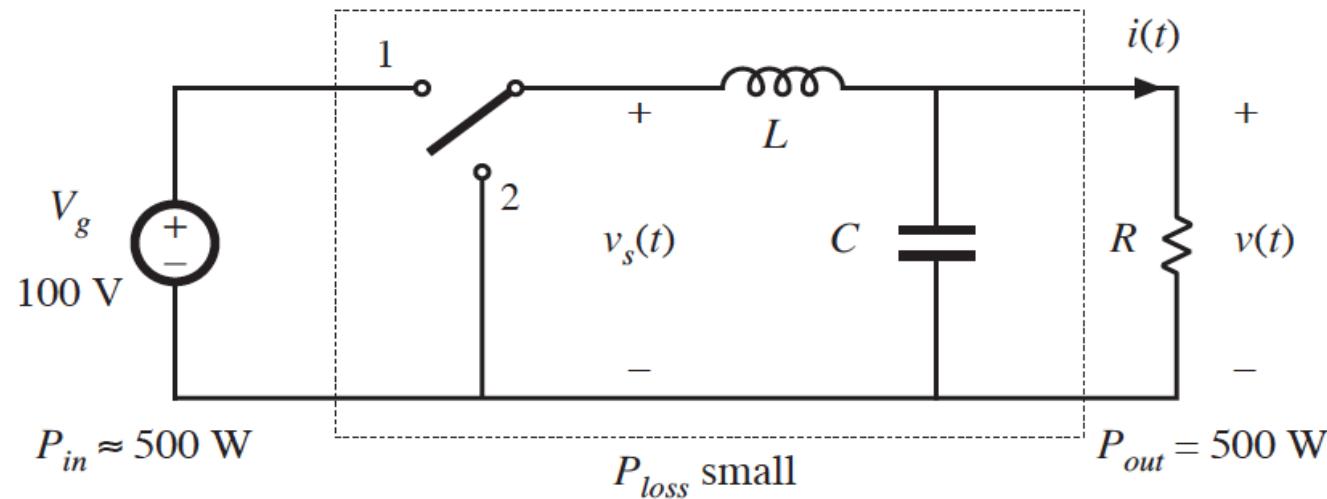
Concept of switching



DC component of $v_s(t)$ = average value:

$$V_s = \frac{1}{T_s} \int_0^{T_s} v_s(t) dt = DV_g$$

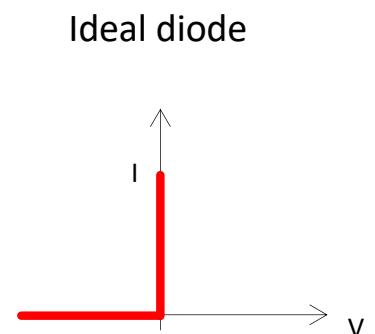
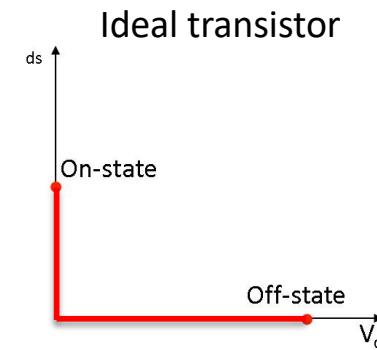
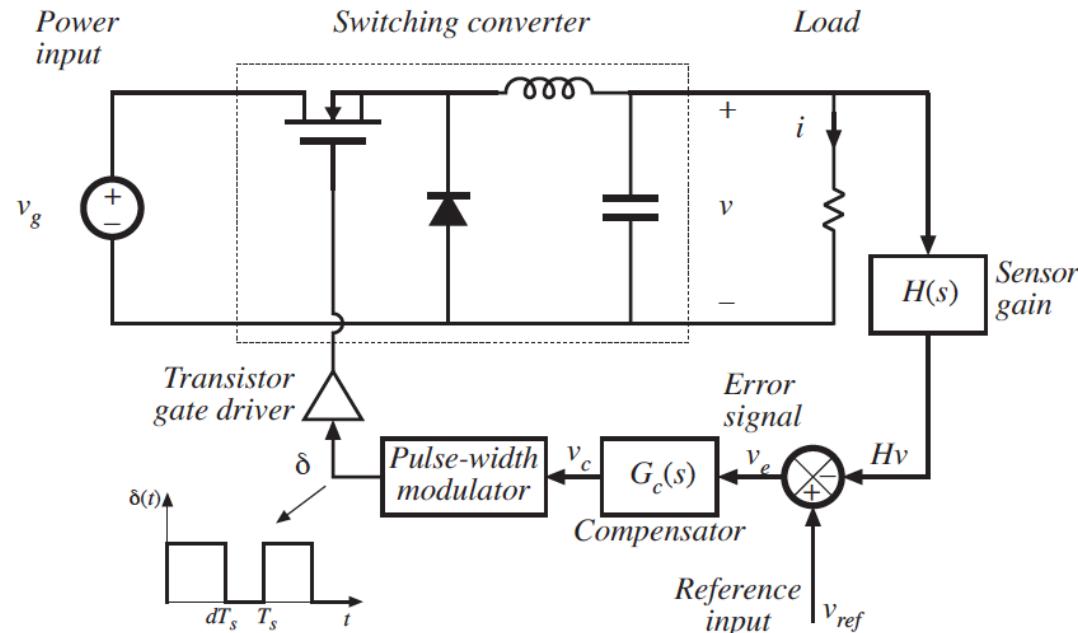
Addition of (ideally lossless) L - C low-pass filter, for removal of switching harmonics:



- Cut-off frequency of the filter must be much smaller than the switching frequency $f_0 \ll f_s$
- This is called a **buck converter**: $V_{out} = DV_{in}$

Realization of such circuit:

Power transistors + power diodes + filters + circuit de regulation



Product $V \times I$ must be as close as possible to zero

Power transistors and diodes are the heart of power converters

They are power switching devices, which:

Should **conduct with small losses, switch fast with small losses, hold large voltages**

Efficient conversion is the goal: **what are the loss mechanisms?**

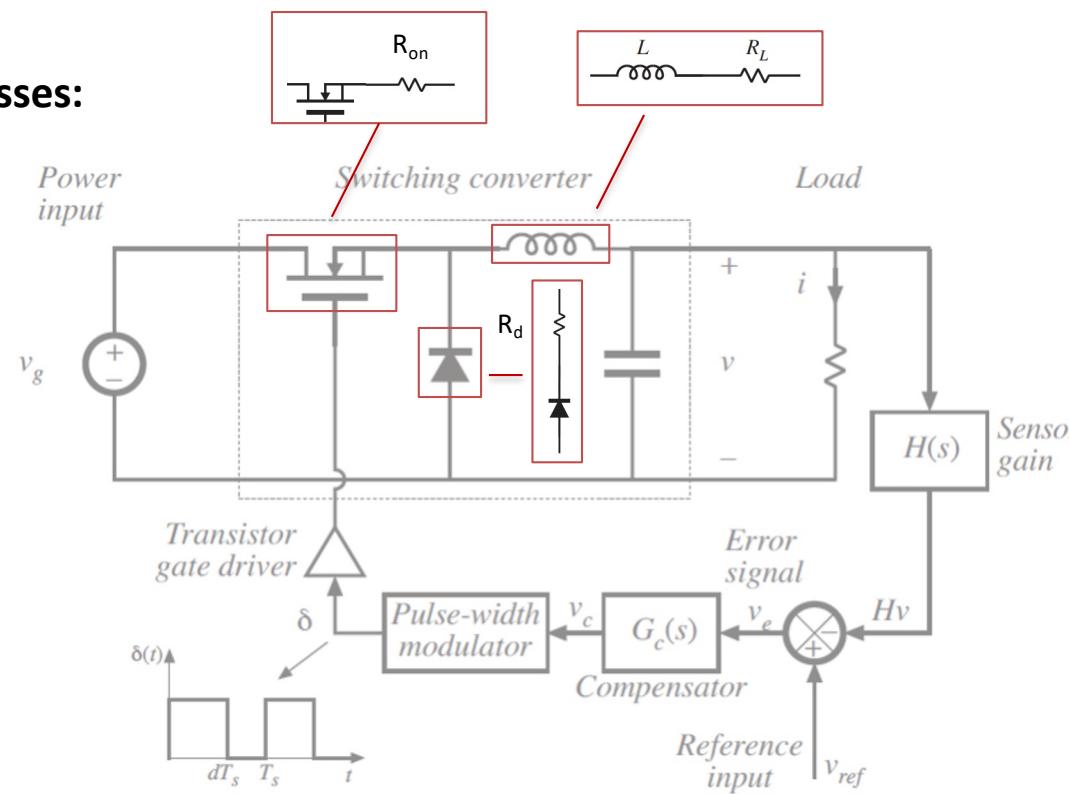
Two main loss mechanisms:

1. **Conduction losses:** when devices are conducting

- Semiconductor forward bias
- Parasitics: inductances, capacitances, resistances

2. **Switching losses:** when devices are switching

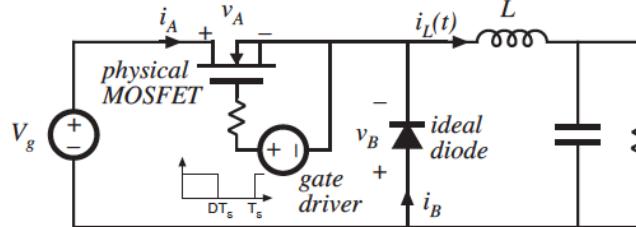
1. **Conduction losses:**



Dissipated power

$$P_{\text{conduction}} = R_{\text{on}} I_{\text{RMS}}^2$$

2. Switching losses:



Buck converter example

$$v_B(t) = v_A(t) - V_g$$

$$i_A(t) + i_B(t) = i_L$$

transistor turn-off
transition

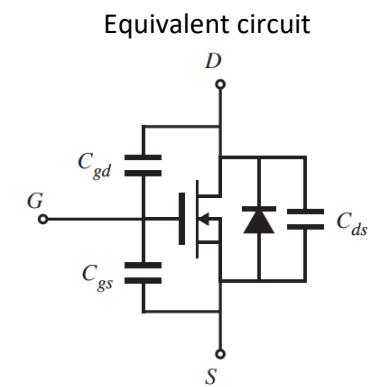
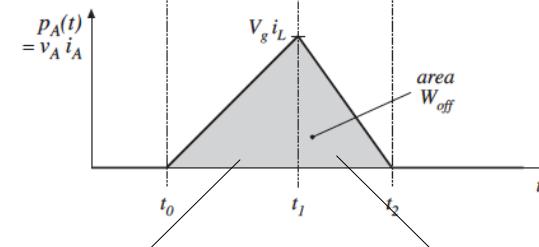
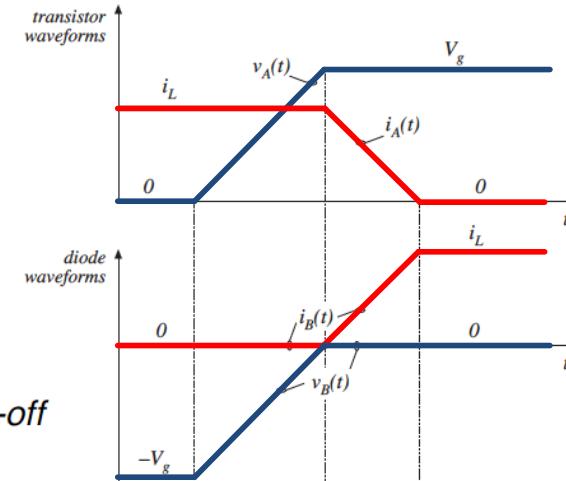
Energy lost during transistor turn-off transition:

$$W_{off} = \frac{1}{2} V_g i_L (t_2 - t_0)$$

Similar result during transistor turn-on transition.

Average power loss:

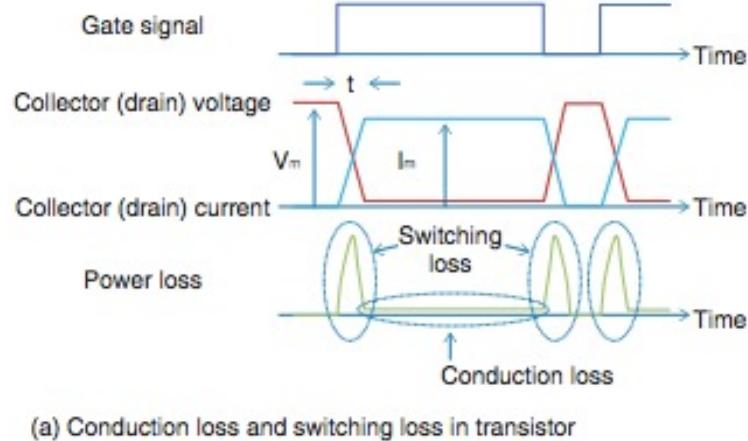
$$P_{sw} = \frac{1}{T_s} \int_{\text{switching transitions}} p_A(t) dt = (W_{on} + W_{off}) f_s$$



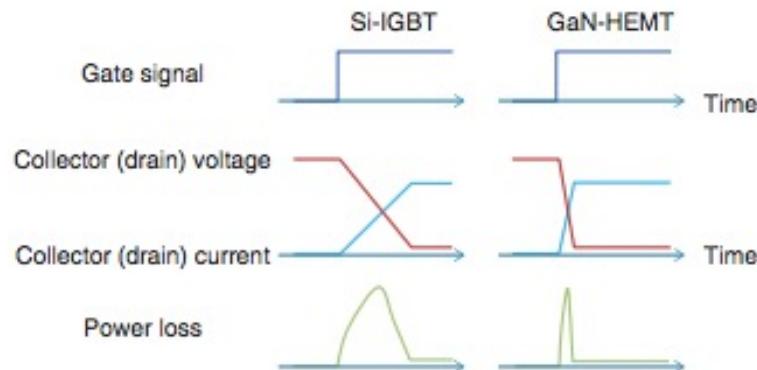
Switching losses are proportional to the switching frequency...

...while conduction losses are fixed

Switching losses

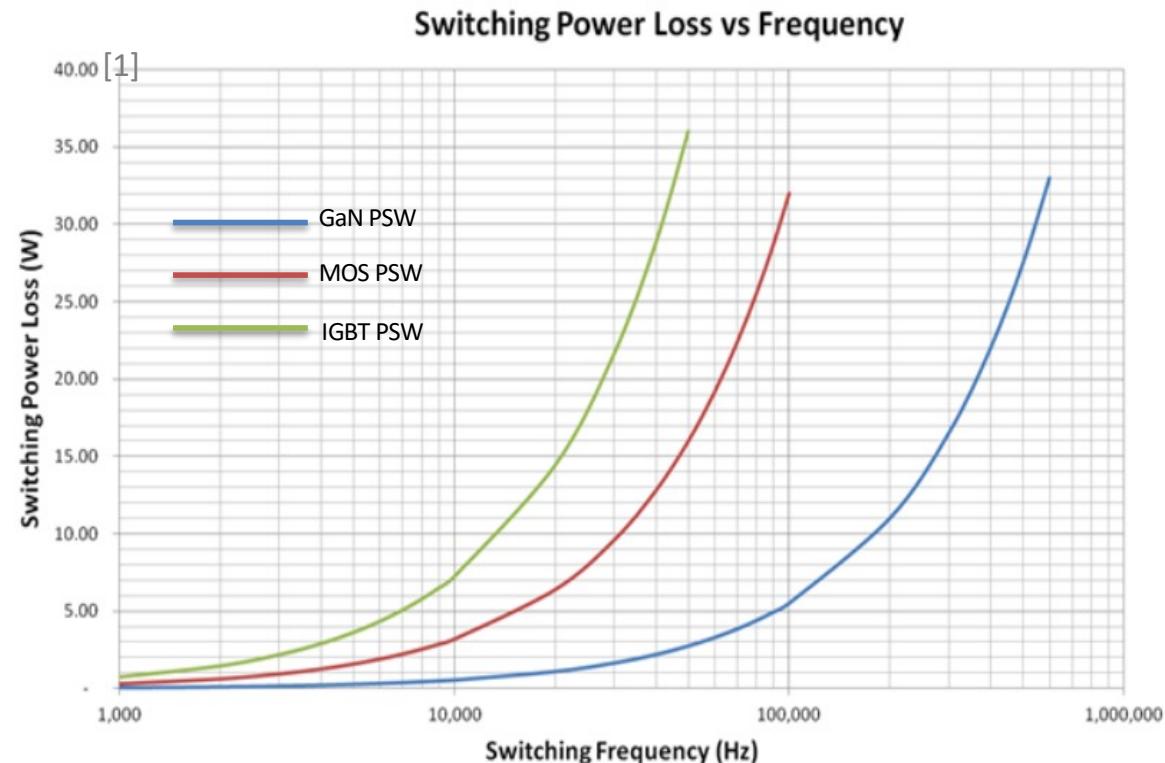


(a) Conduction loss and switching loss in transistor



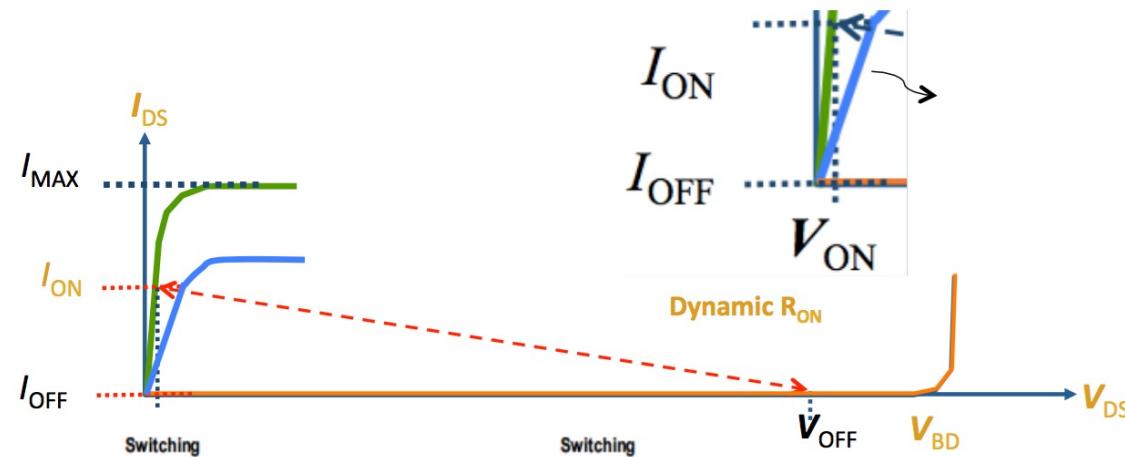
The power loss can be reduced in GaN-HEMT, which has a shorter switching time than Si-IGBT.

(c) Comparison of switching properties of Si-IGBT and GaN-HEMT



Switching losses are proportional to the switching frequency: Fast devices are required!

Power switch:

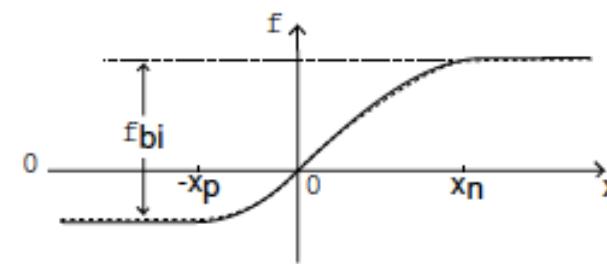
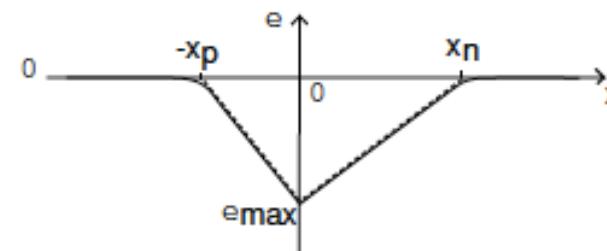
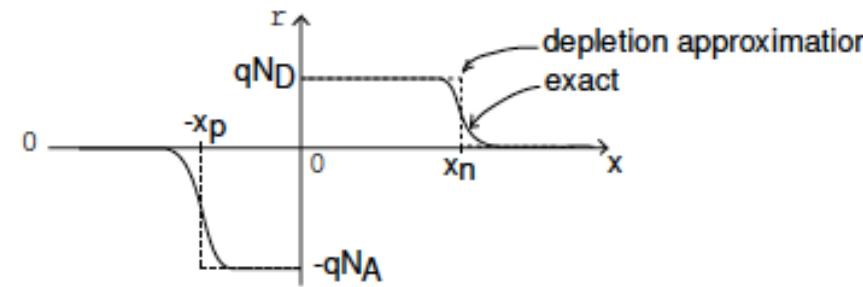
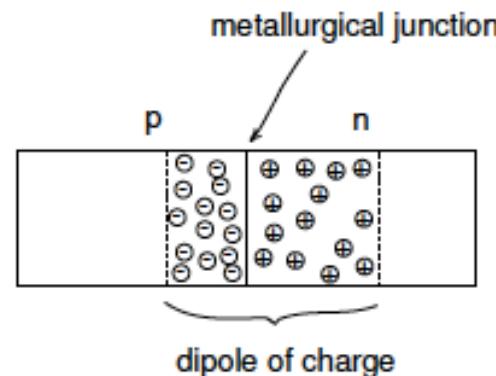


It operates in two regimes:
 ON: Low voltage, high current
 OFF: High voltage, low current

- High breakdown voltage
- Low on-resistance: Small on-state power dissipation: $I_{rms}^2 \times R_{on}$
- High maximum current
- Low leakage current at breakdown voltage: Small off-state power dissipation: $I_{off} \times V_{br}$

How to get large breakdown voltages?

Back to pn junctions



Distinct regions:

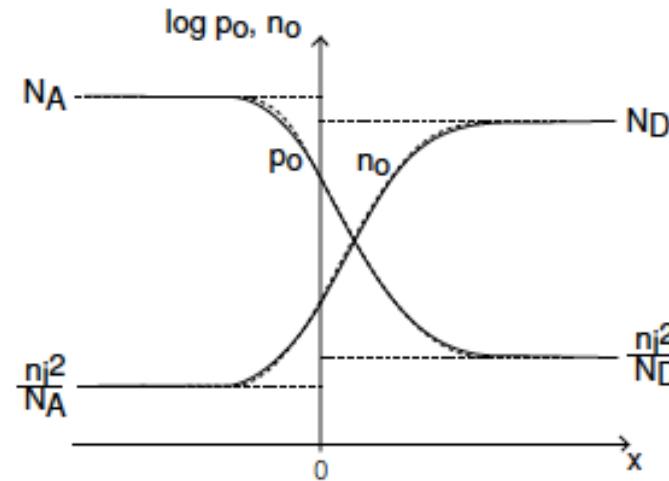
Around metallurgical junction:
space charge region (SCR)

Far from junction:

quasi-neutral regions (QNR)

$\rho \sim 0$

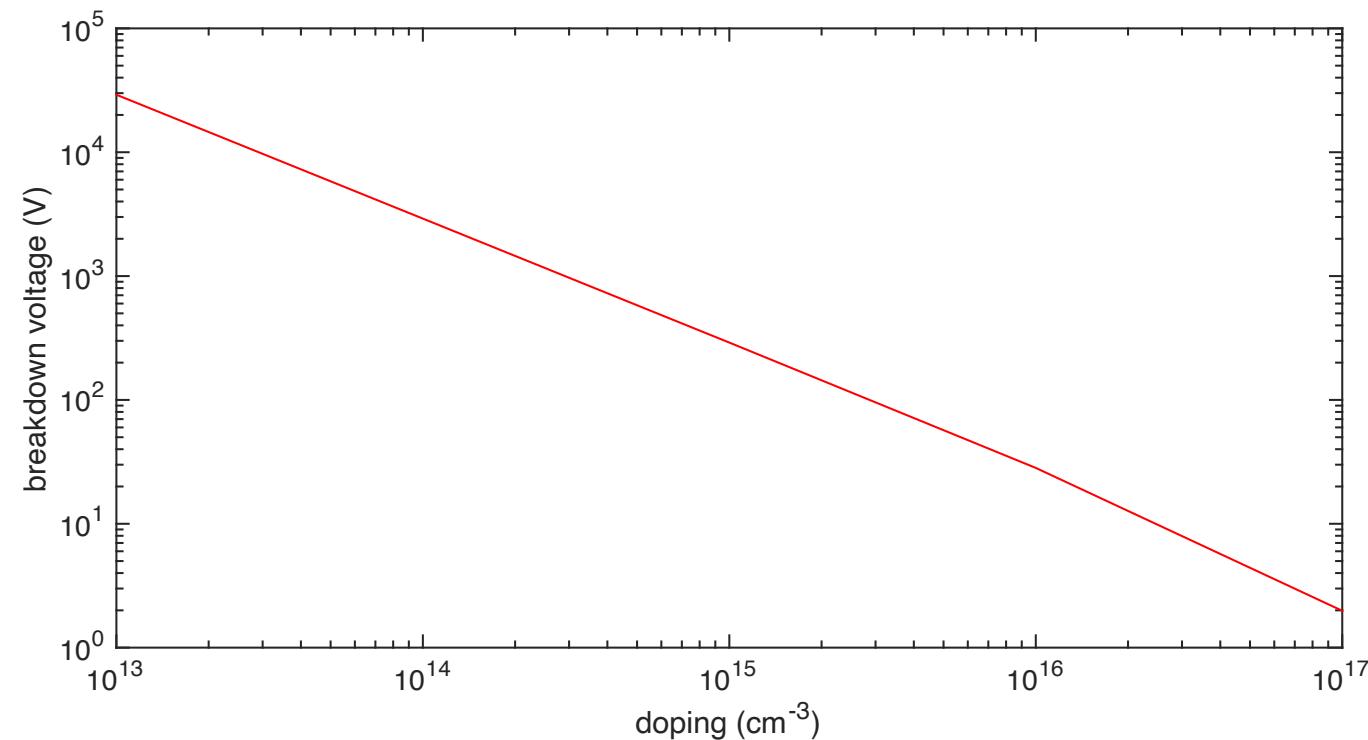
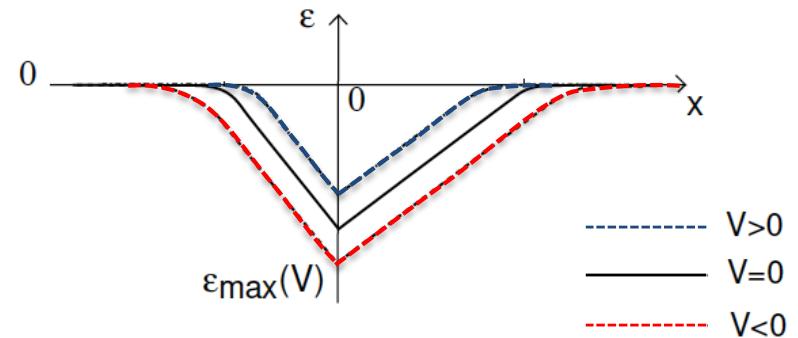
Electric field is constant and equal to zero



Ideal p-n junction out of equilibrium

Peak electric field:

$$|\mathcal{E}_{max}(V)| = \sqrt{\frac{2qN_A N_D(\phi_{bi} - V)}{\epsilon(N_D + N_A)}} = |\mathcal{E}_{max}(V = 0)| \sqrt{1 - \frac{V}{\phi_{bi}}}$$



How to make a power device?

Goal:

Conduct **several kilo amps** of current in the forward direction with very **little power loss** while blocking **several kilo volts** in the reverse direction.

Large blocking voltage requires **wide depletion layer** in order to restrict the maximum electric field strength below the breakdown voltage (impact ionization level).

Space **charge density in the depletion layer should also be low** in order to yield a wide depletion layer for a given **maximum electric field strength**.

This is satisfied in a **lightly doped p-n junction diode of sufficient width** to accommodate the required depletion layer.

PIN diode

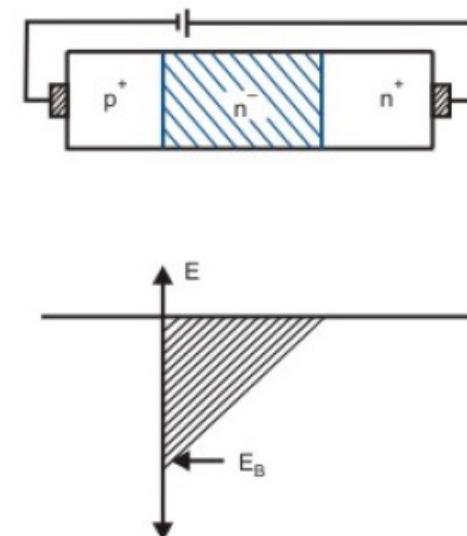
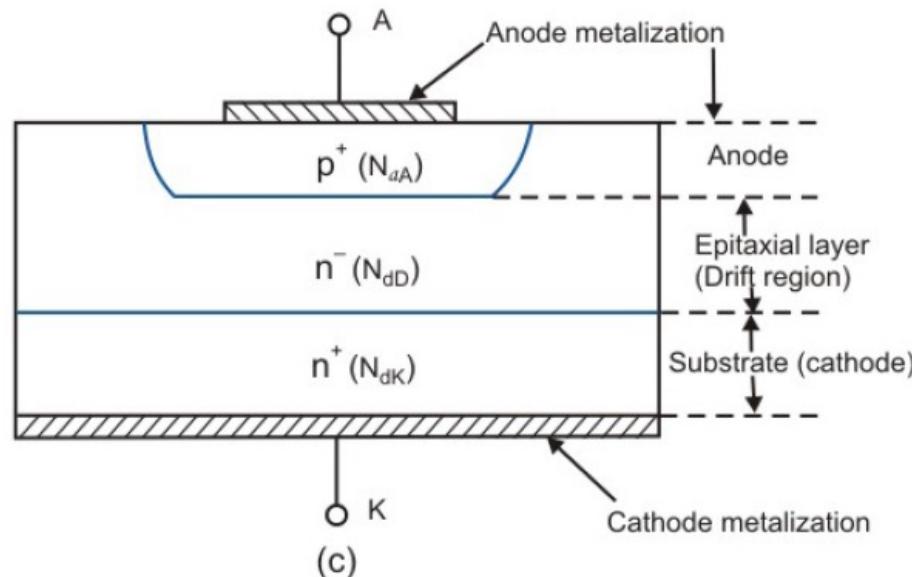
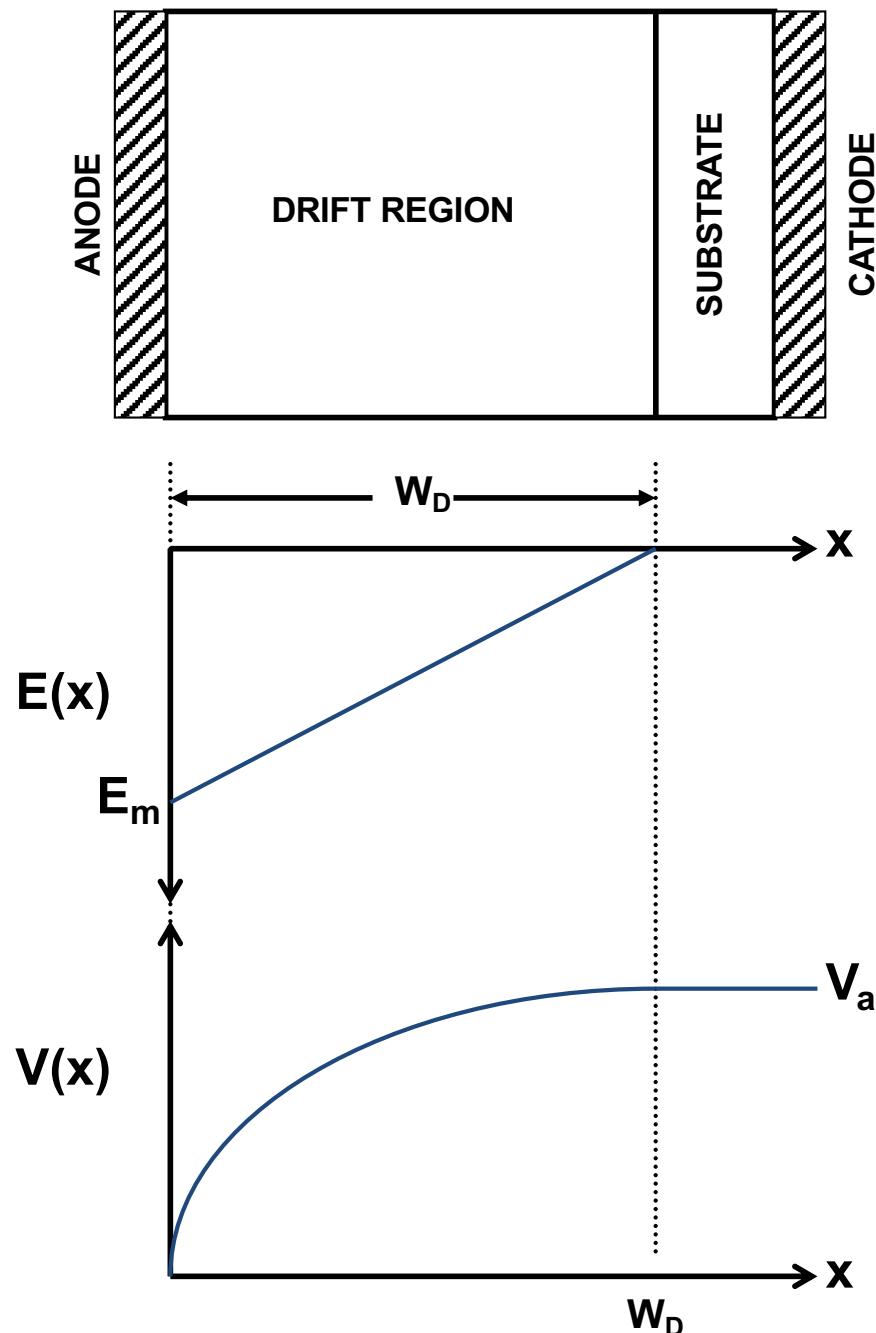


Figure of merit: how to compare different semiconductors



Specific on-resistance (Ωcm^2)

$$R_{ON,SP} = \frac{W_D}{qN_D\mu_n}$$

$$V = \frac{E_m W_D}{2} \quad \text{thus}$$

$$W_D = \frac{2BV}{E_C}$$

Poisson's Equation:

$$\frac{d^2V}{dx^2} = -\frac{dE}{dx} = -\frac{Q(x)}{\epsilon_S} = -\frac{qN_D}{\epsilon_S}$$

$$E(x) = -\frac{qN_D}{\epsilon_S}(W_D - x)$$

$$V(x) = \frac{qN_D}{\epsilon_S}(W_D x - \frac{x^2}{2})$$

$$V_a = \frac{qN_D W_D^2}{2\epsilon_S}$$

$$N_D = \frac{\epsilon_S E_C^2}{2qBV}$$

Ideal Specific On-Resistance ($R_{ON,SP}$):

$$W_D = \frac{2BV}{E_C} \quad \text{and} \quad N_D = \frac{\epsilon_s E_C^2}{2qBV}$$

$$R_{ON,SP} = \frac{W_D}{q\mu_n N_D}$$

$$R_{ON,SP} = \frac{4BV^2}{\epsilon_s \mu_n E_C^3}$$

$R_{on,sp}$ is related to material properties

Baliga's figure of merit

$$BFOM = \epsilon_s \mu_n E_C^3 = \frac{4BV^2}{R_{ON,SP}}$$

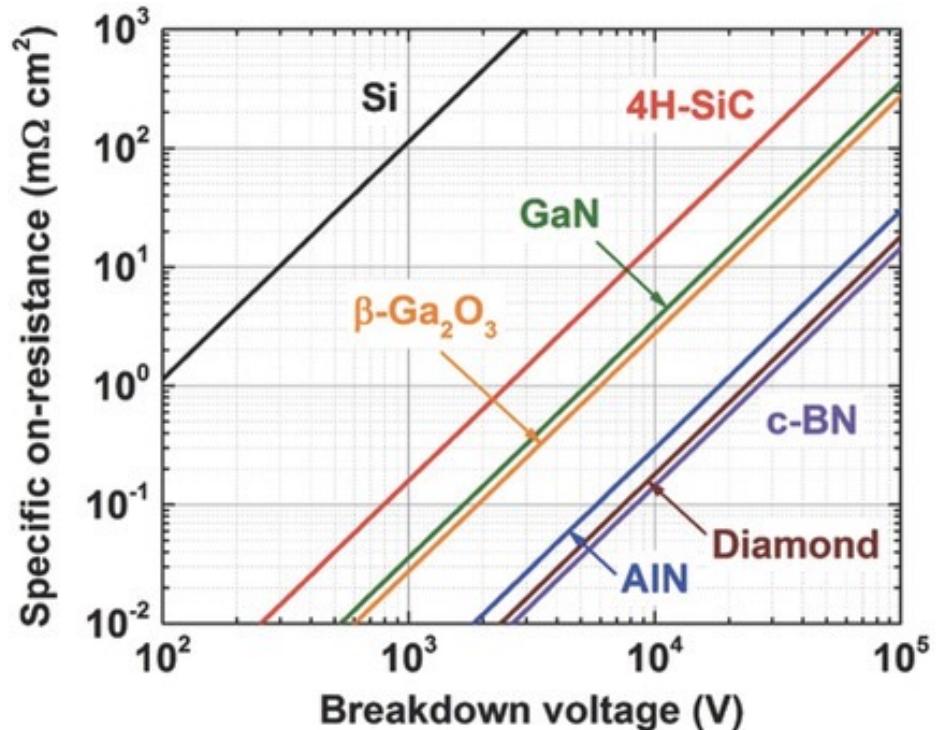
Critical electric field E_c is very important, followed by mobility in the drift layer

$$R_{ON,SP} = \frac{4BV^2}{\epsilon_S \mu_n E_C^3}$$

$R_{on,sp}$ is related to material properties

Baliga's figure of merit

$$BFOM = \epsilon_S \mu_n E_C^3 = \frac{4BV^2}{R_{ON,SP}}$$



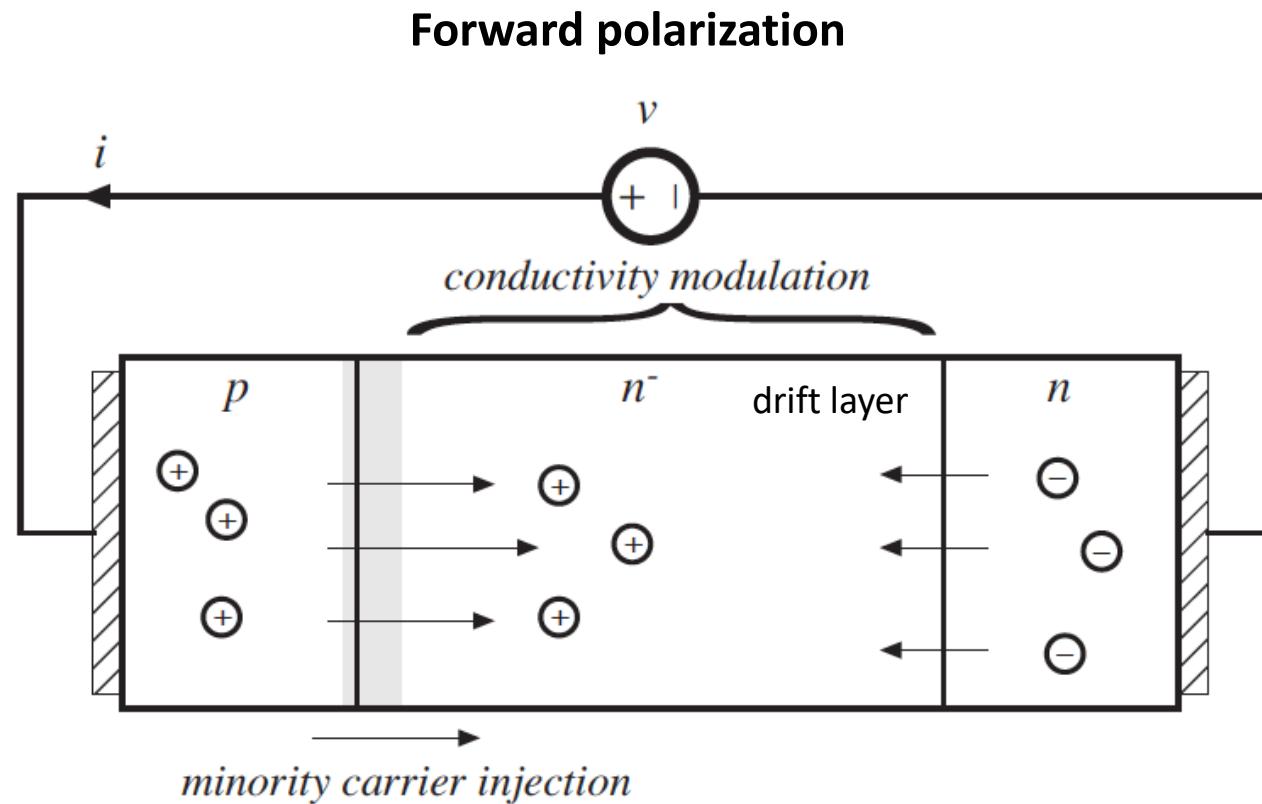
Parameter	Silicon	4H-SiC	GaN	Diamond
E_g , eV	1.12	3.26	3.39	5.47
E_{crit} , MV/cm	0.23	2.2	3.3	5.6
ϵ_r	11.8	9.7	9.0	5.7
μ_n , cm²/V·s	1400	950	800/1700 ^b	1800
BFoM ^a relative to Si	1	500	1300/2700 ^b	9000
n_i , cm ⁻³	$1 \cdot 10^{10}$	$8 \cdot 10^{-9}$	$2 \cdot 10^{-10}$	$1 \cdot 10^{-20}$
λ , W/cm·K	1.5	3.8	$1.3/3^c$	20

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Desired properties, found in some of these wide band-gap materials:

- Higher breakdown strength: same breakdown voltage with less material
- Higher switching speed: lower switching losses
- Lower losses: enables significantly reduced volume and decreased cooling requirements
- Higher frequency: smaller passive components (inductors and capacitors)

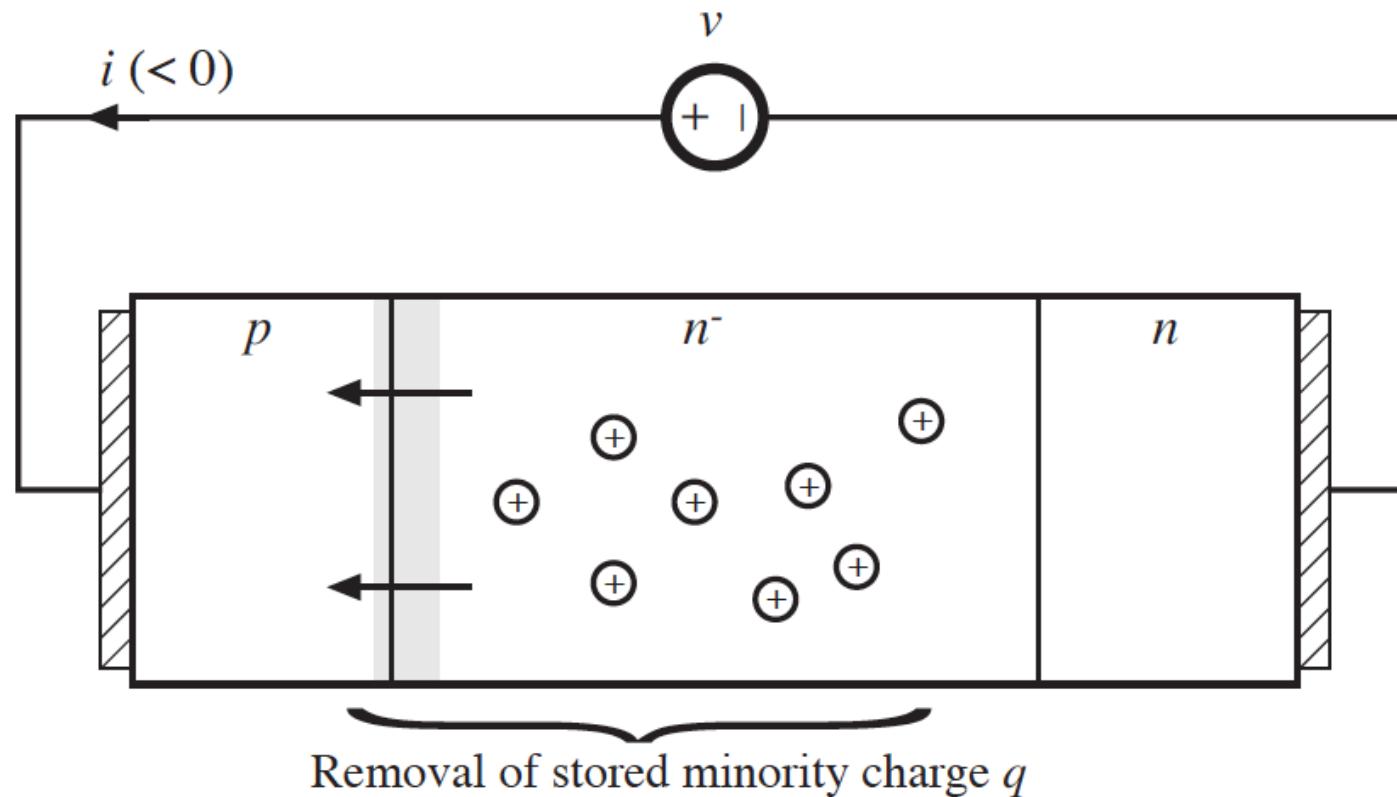
diode PIN

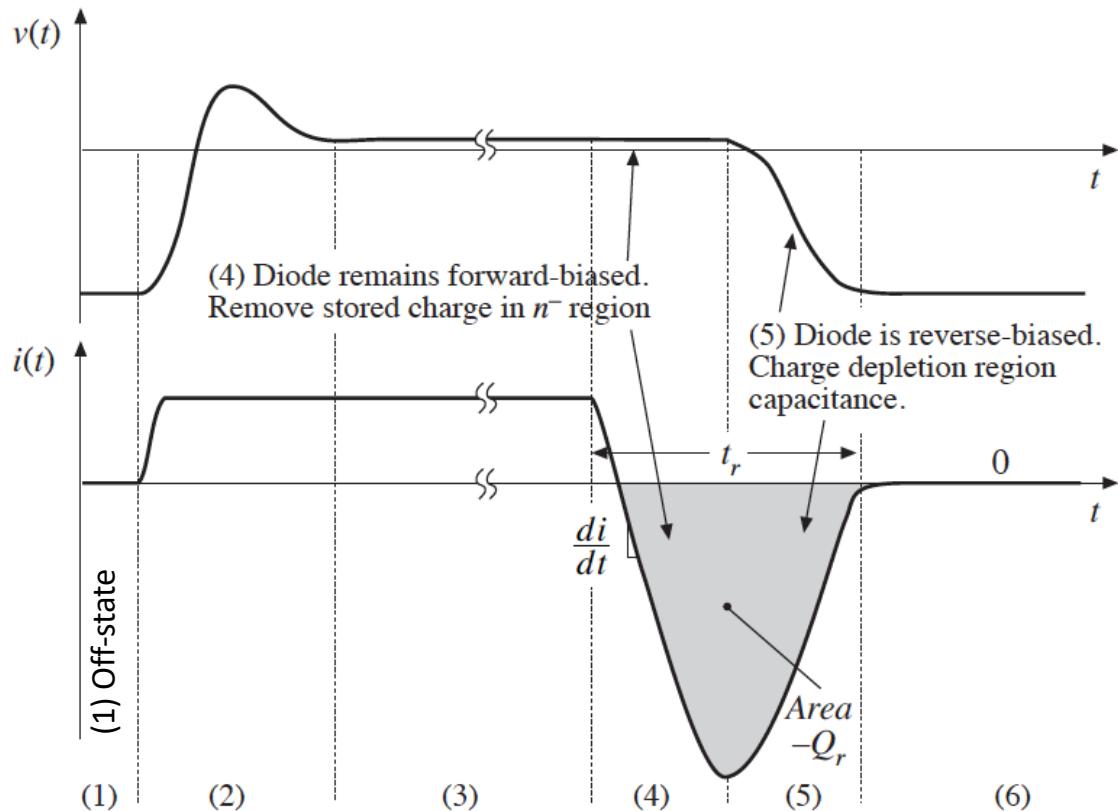


Forward polarization:

- Injection of minority carriers in the drift layer: conductivity modulation
- Charges are accumulated in the region «i»:
 - Resistance is reduced
 - But slows down the device
- Minority carrier device

Turn-off transient





(4) Reduction of the stored minority charge can be accomplished either by active means, via **negative terminal current**, or by passive means, via **recombination**. Normally, both mechanisms occur simultaneously.

The charge contained in the negative portion of the diode turn-off current waveform is called the **recovered charge**.

Minority charges are actively-removed during interval (4).

At the end of interval (4), the stored minority charge in the vicinity of the **junction has been removed**, such that the diode junction becomes **reverse-biased** and is able to **block negative voltage**.

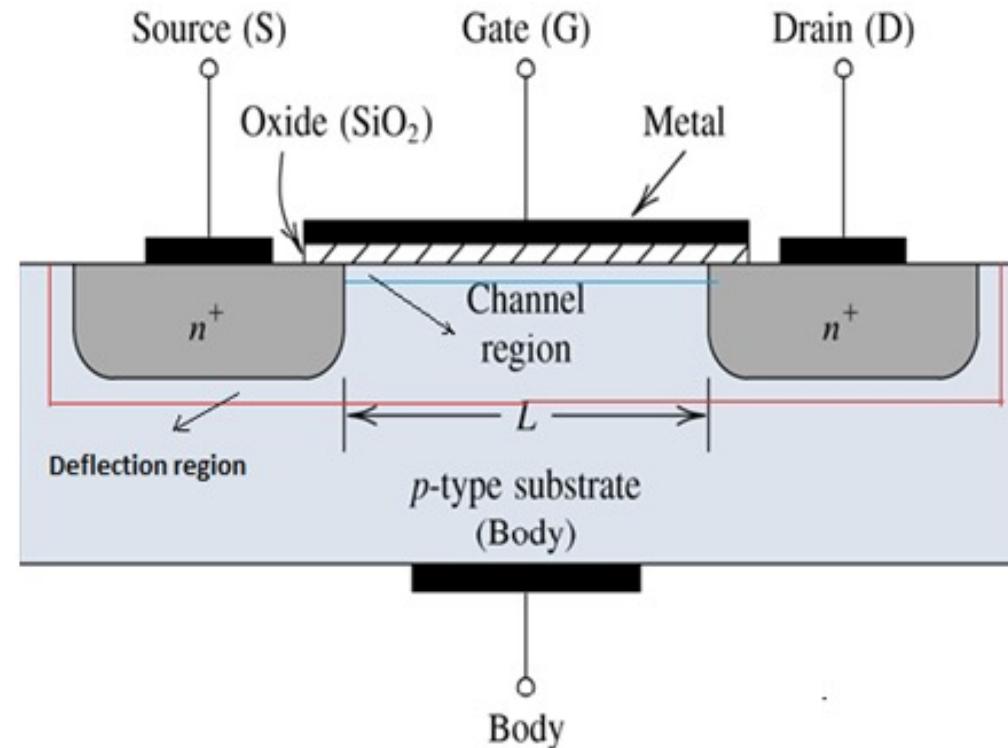
The depletion region **effective capacitance** is then **charged** during interval (5) to the negative off-state voltage.

The portion of Q during interval (5) is **charge supplied to the depletion region**, as well as minority charge that is actively removed from remote areas of the diode.

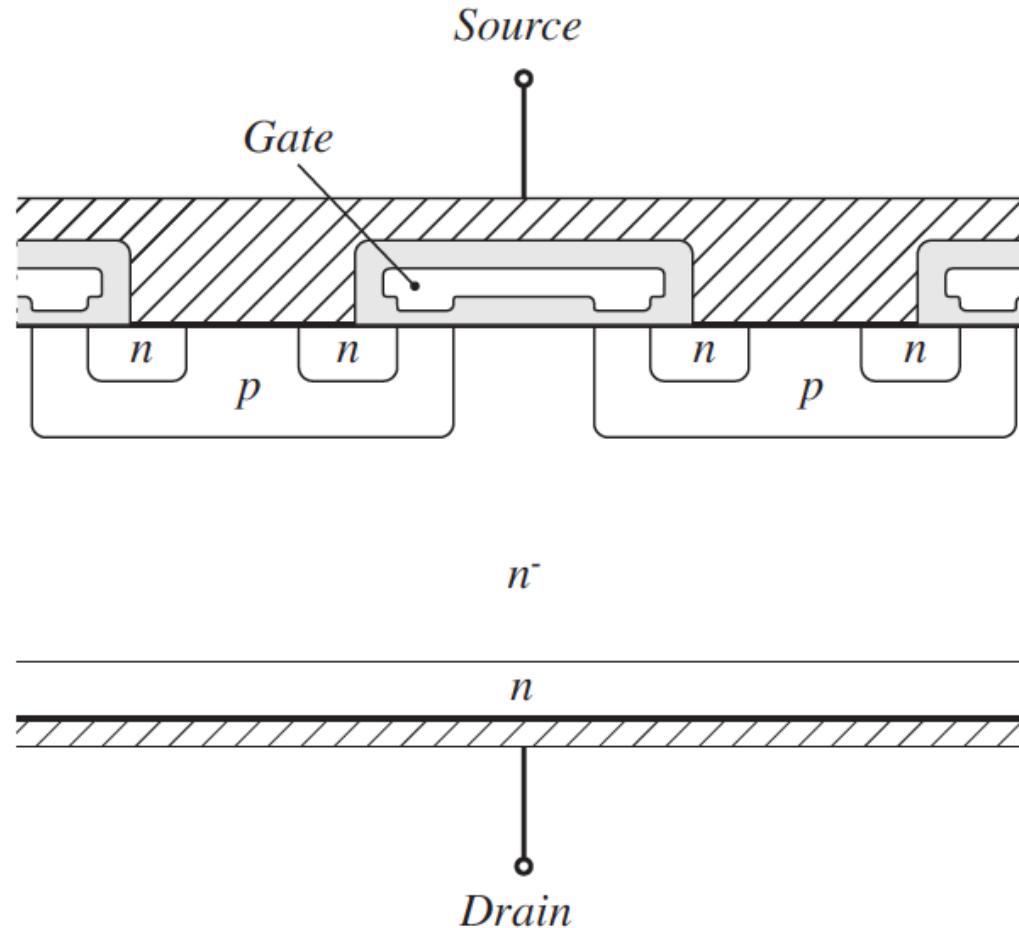
At the end of interval (5), the diode is able to **block the entire applied reverse voltage**.

The length of intervals (4) and (5) is the **reverse recovery time t_r**

Q_r: reverse recovery charges: diode is very slow!

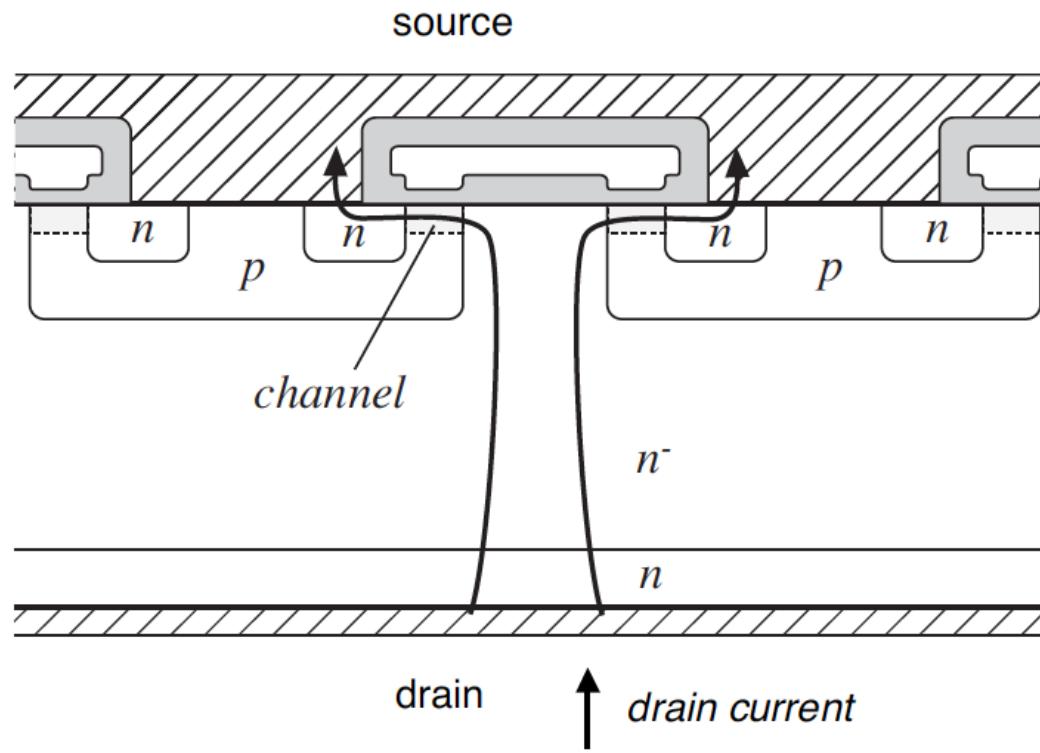


How to make a power MOSFET?



- Gate lengths approaching one micron
- Consists of many small enhancement-mode parallel-connected MOSFET cells, covering the surface of the silicon wafer
- Vertical current flow
- n-channel device is shown

Forward polarization: $V_{gs} > 0$

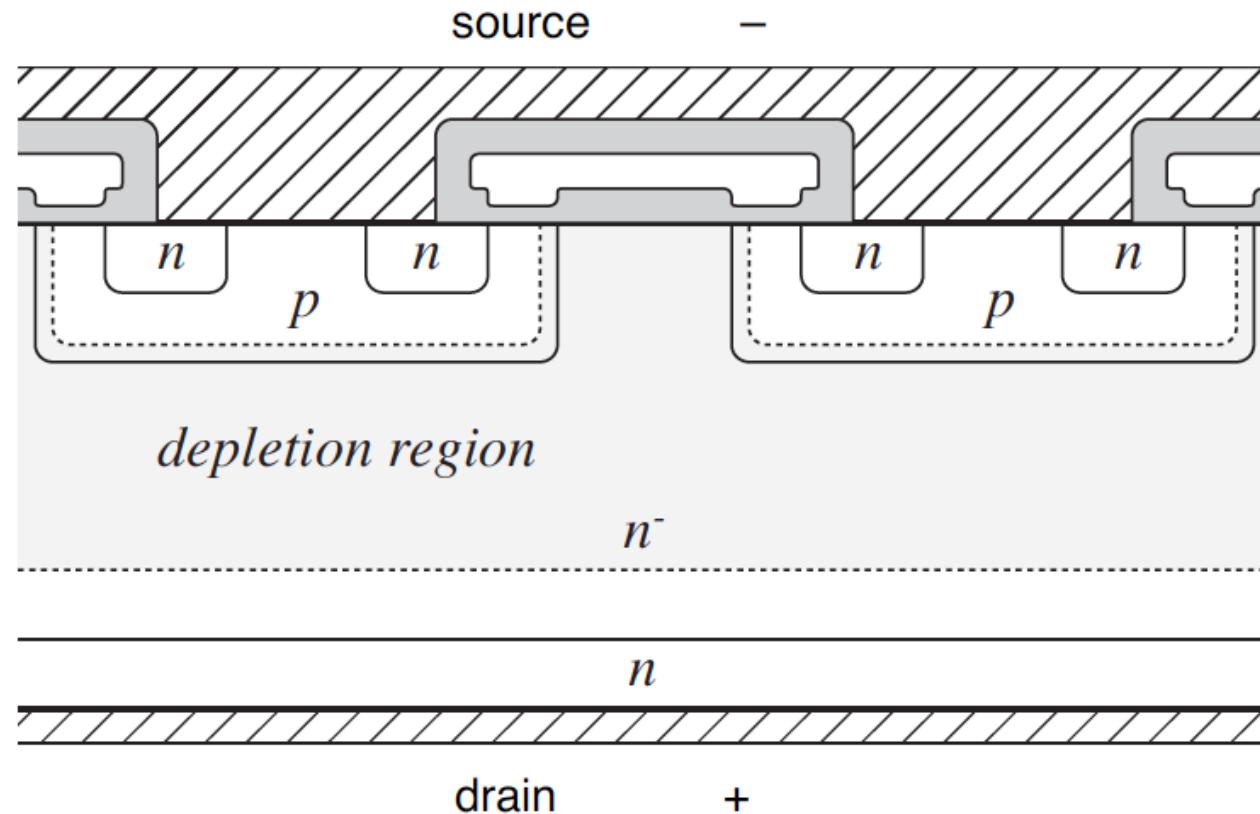


- $p-n^-$ junction is slightly reverse-biased
- positive gate voltage induces conducting channel
- drain current flows through n^- region and conducting channel
- on resistance = total resistances of n^- region, conducting channel, source and drain contacts, etc.

There are no minority carriers to cause conductivity modulation: **MOSFETs are majority carrier devices**

- Breakdown voltage is increased
- On-resistance dominated by resistance of n^- region.

Reverse polarization: $V_{gs} < 0$

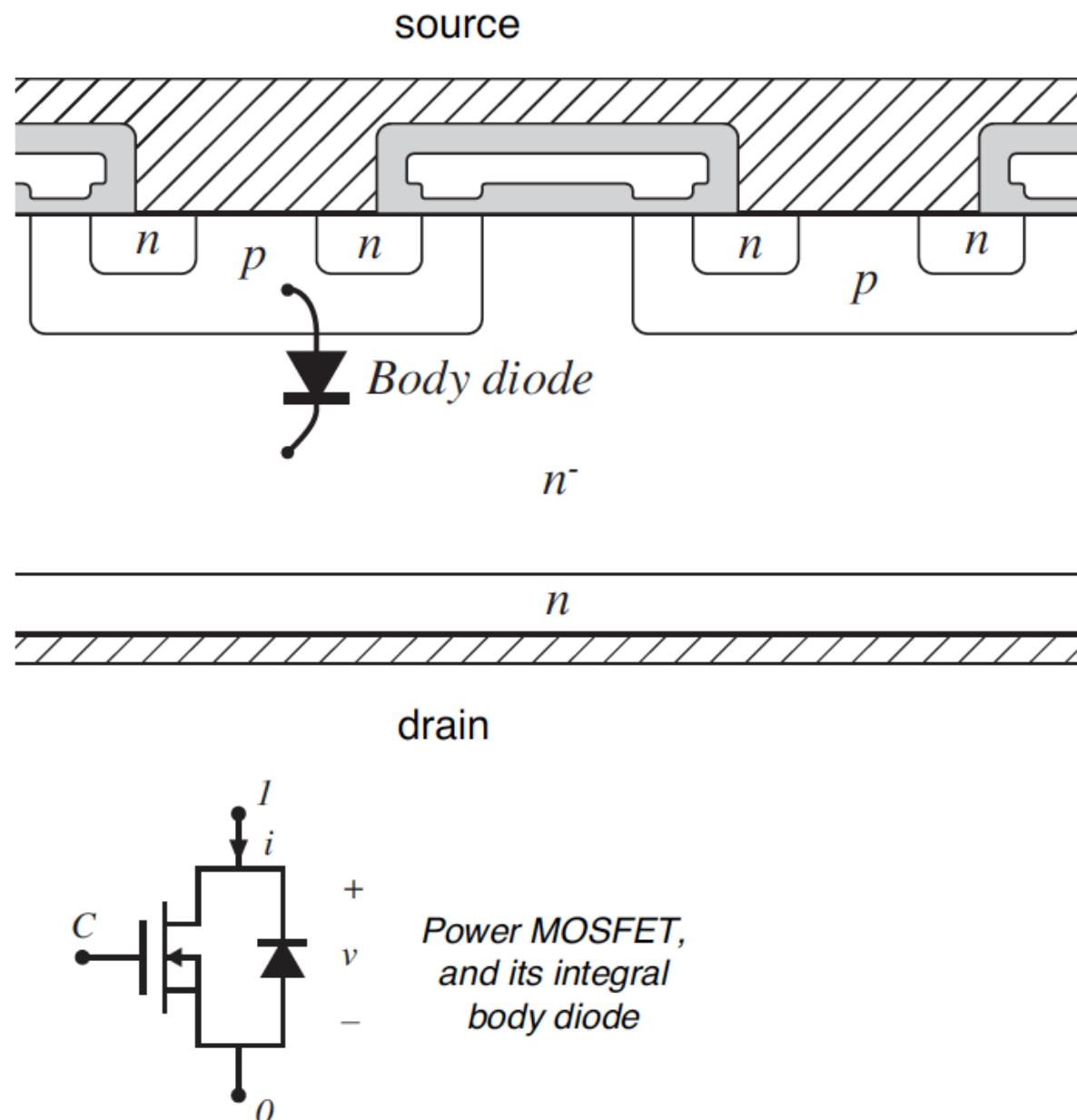


- $p-n^-$ junction is reverse-biased
- off-state voltage appears across n^- region

Polarisation reverse:

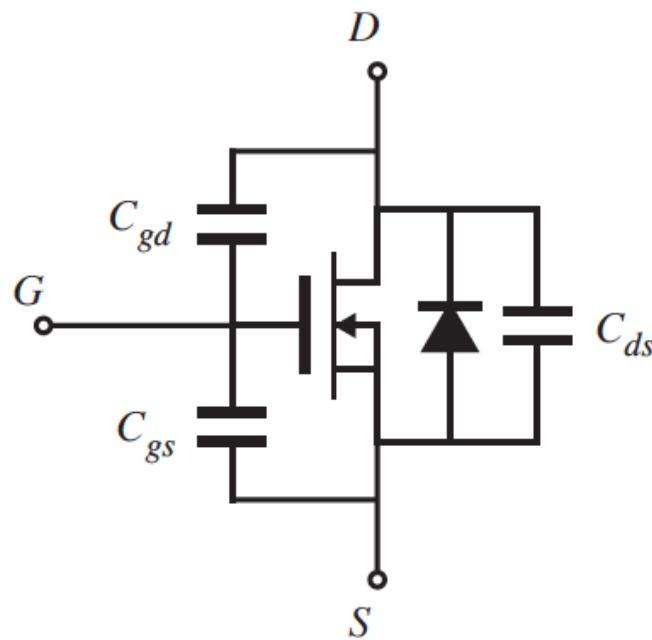
$p-n$ and $p-n^-$ reverse-biased: voltage drops across n^- region

MOSFET: body-diode



- $p-n^-$ junction forms an effective diode, in parallel with the channel
- negative drain-to-source voltage can forward-bias the body diode
- diode can conduct the full MOSFET rated current
- diode switching speed not optimized —body diode is slow, Q_r is large

MOSFET: equivalent circuit



- C_{gs} : large, essentially constant
- C_{gd} : small, highly nonlinear
- C_{ds} : intermediate in value, highly nonlinear
- switching times determined by rate at which gate driver charges/discharges C_{gs} and C_{gd}

$$C_{ds}(v_{ds}) = \frac{C_0}{\sqrt{1 + \frac{v_{ds}}{V_0}}}$$

$$C_{ds}(v_{ds}) \approx C_0 \sqrt{\frac{V_0}{v_{ds}}} = \frac{C_0}{\sqrt{v_{ds}}}$$

C_{gd} is small but the voltage is large: so a lot of charges stored